[Chamber A]
Process: P-TEOS/TMP
Hard: CVD
Gas(sccm): Ar(7000), Ar(500), He(2000), N2(5000), NF3(3000), 02(3000), TEOS(300), TMP(60)
RPU: 400kHz/3000W
HRF: 13.56MHz/1000W
LRF: 430kHz/1000W

[Chamber B]
Process: P-TEOS/TMP
Hard: CVD
Gas(scm): Ar(7000), Ar(500), He(2000), N2(5000), NF3 (3000), 02(3000), TEOS(300), TMP(60)
RPU: 400kHz/3000W
HRF: 13.56MHz/1000W
LRF: 430kHz/1000W

[Chamber C]
Process: P-TEOS/TMP
Hard: CVD
Gas(scm): Ar(7000), Ar(500), He(2000), N2(5000), NF3(3000), 02(3000), TEOS(300), TMP(60)
RPU: 400 kHz/3000W
HRF: 13.56MHz/1000W
LRE: 430kHz/1000W